

Amendments to the Claims:

1.(Previously Amended) A method for forming at making an organic transistor on a substrate comprising the steps of:

providing a substrate including a metal surface layer;

providing a rotatable stamp having relief geometries on its surface to define a stamping surface;

applying a self-assembled monolayer ink to the surface of the rotatable stamp to define an inked stamping surface;

rotating the rotatable stamp on the metal surface layer as the layer is placed in contact with the stamp to impress on the layer an inked pattern as defined by the inked stamping surface; and

patterning the layer by etching material from the layer wherein the inked stamping surface guides the etching in a geometry to define the patterned layer useful in fabricating an electronic device;

removing the inked pattern from the layer; and

applying an organic semiconductor layer overlying the etched metal layer.

2.(Canceled)

3.(Original) The method of claim 1, in which the step of providing the rotatable stamp comprises:

(a) casting a liquid onto a surface having relief geometries thereon;

(b) solidifying the liquid to define a solid film; and

(c) rolling a member over the solid film so that the solid film is lifted from the surface and bonds to the member.

4.(Original) The method of claim 3, in which the liquid comprises an elastomeric material, the step of solidifying the liquid comprises curing the elastomeric material to form an elastomeric film.

5.(Original) The method of claim 4, further comprising a step of exposing the cured elastomeric film to oxygen plasma before the member is rolled over the film.

6.(Canceled)

7.(Currently Amended) The method of claim [6] 1 in which the metal surface layer [at least one coating layer] includes a thin layer of gold or silver.

8.(Previously Amended) The method of claim 1 in which the step of patterning the metal layer comprises etching material from the substrate applying an etchant selected from the group consisting of aqueous ferrocyanide, $K_4Fe(CN)_6$, $K_3Fe(CN)_6$, $Na_2S_2O_3$, and KOH in H_2O .

9.(Original) The method of claim 1, in which the step of rotating the stamp provides an exposed region on the metal layer where substantially no ink is present and a protected region on the layer where ink substantially covers protected region.

10.(Canceled)

11. The method of claim [10] 1, in which the metal surface layer has an applied adhesive layer selected from the group consisting of Ti and Cr.

12.(Previously Amended) The method of claim 1 in which the inked pattern is removed by ultraviolet light, heat, or wet chemical cleaning.

13.(Canceled)

14.(Canceled)

15.(Canceled)

19.(Previously Amended) The method of claim 3 wherein the member comprises a cylinder with a glass surface.

20.(Canceled)

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21.(Canceled)

22.(Canceled)